

IN THE CLAIMS:

Claims 1-21. Canceled.

22. (Currently Amended) An apparatus for surface treatment comprising:

a processing vessel in which an object to be processed is placed;

[[means]] a ClF₃ supplier for supplying ClF₃ gas into the processing vessel;

[[means]] a promoter for promoting adhesion of ClF₃ gas to a surface of the
object to be processed;

an evacuator for evacuating ClF₃ gas from the processing vessel; and

[[means]] an activator for activating ClF₃ gas ~~supplied in the processing vessel~~
adhered to the surface of the object so as to remove an oxide formed on the surface of
the object by using the ClF₃ adhered to the surface of the object.

23. (Previously Presented) An apparatus for surface treatment according to claim 22,
further comprising a mount located in the processing vessel for setting the object to be
processed thereon.

24. (Currently Amended) An apparatus for surface treatment according to claim 23,
wherein the ~~means for promoting adhesion of the ClF₃ gas to the object to be processed~~
promoter is provided in the mount, ~~the means for promoting adhesion thereby cooling~~
the object to be processed on the mount.

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25. (Currently Amended) An apparatus for surface treatment according to claim 24, wherein the ~~means for activating the ClF_3 gas~~ activator heats the object to be processed in a heating position at a distance from an object setting position of the object on the mount.

26. (Currently Amended) An apparatus for surface treatment according to claim 25, further comprising ~~means for elevating and lowering~~ an elevator for moving the object to be processed up and down between the object setting position and the heating position.

27. (Currently Amended) A cluster device comprising[:] the apparatus for surface treatment according to claim [[21]] 22, and further comprising:

a transport chamber for maintaining a non-reactive atmosphere therein and for transporting an object to be processed in the non-reactive atmosphere to and from the apparatus for surface treatment; and

at least one processing apparatus for transporting the object to be processed to and from the transport chamber.

28. (Original) The cluster device according to claim 27, wherein the apparatus for surface treatment is a metal wiring formation chamber for making metal wiring on the object to be processed.

29. Canceled.

30. Canceled

31. Canceled.

32. Canceled.

33. (New) A cluster device comprising:

a transport chamber for maintaining a non-reactive atmosphere therein and for transporting an object to be processed in the non-reactive atmosphere to and from an apparatus for surface treatment;

at least one processing apparatus for transporting the object to be processed to and from the transport chamber; and

an apparatus for surface treatment including

a processing vessel in which an object to be processed is placed;

a ClF_3 supplier for supplying ClF_3 gas into the processing vessel;

an activator for activating the ClF_3 gas supplied in the processing vessel; and

a reducer supplier for supplying a reducing gas into the processing vessel.

34. (New) A cluster device according to claim 33, wherein the apparatus for surface treatment is a metal wiring formation chamber for making metal wiring on the object to be processed.

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35. (New) An apparatus for surface treatment according to claim 22, further comprising a reducer supplier for supplying a reducing gas into the processing vessel.

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